

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of

Atty. Docket

RENE MONSHOUWER ET AL

NL 000770

Serial No.

Filed: CONCURRENTLY

METHOD OF MEASURING ALIGNMENT OF A SUBSTRATE WITH RESPECT TO  
A REFERENCE ALIGNMENT MARK

Commissioner for Patents  
Washington, D.C. 20231

PRELIMINARY AMENDMENT

Sir:

Prior to calculation of the filing fee and examination,  
please amend the above-identified application as follows:

IN THE SPECIFICATION

**Page 21, in the paragraph beginning on line 9,**

With an off-axis alignment-measuring device, for  
example that of Fig. 8, not only the position of a substrate  
but also the position of the substrate holder or substrate  
table can be measured. To this end, the holder or table is  
also provided with an alignment mark similar to the global  
substrate alignment mark. If the position of the substrate  
holder with respect to the reference in the alignment-  
measuring device has been determined, the position of the  
substrate mark with respect to the substrate holder mark will  
be known. To be able to determine the mutual position of the  
mask pattern and the substrate, a further measurement is  
necessary, namely that of the position of the mask pattern  
with respect to the substrate holder or table. For this

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